IAP20 Recid ROTATIO 3 1 JAN 2006 IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

| Application Şerial No | unknown |
|--|------------------------------|
| Confirmation No | unknown |
| Filing Date | unknown |
| Inventor | J. Kim |
| Assignee | Honeywell International Inc. |
| Group Art Unit | unknown |
| Examiner | unknown |
| Attorney's Docket No | H0006155 USA |
| Customer No | 021567 |
| Title: Methods Of Treating Deposition Process Components To Form Particle Traps, And Deposition Process Components Having Particle Traps Thereon | |

PRELIMINARY AMENDMENT

To:

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

From:

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AMENDMENTS